

ABSTRACT

A polishing pad (2) includes a polishing layer (20). The polishing layer (20) includes a polyurethane obtained by reacting a multifunctional isocyanate, a polyol composition, and a polyamine composition. The polyamine composition includes one and/or more of diamines and/or triamines and/or polyamines with more than 3 aminos. An average molecular weight of the polyamine composition is between 200 and 400. An average functionality of the polyamine composition is greater than 2 and not higher than 2.20. Proportions of the diamines and the triamines relative to the total amount of the polyamine composition are 77%-96% : 3%-12%, respectively, in the polyamine composition. The polishing pad has a higher controllability, lower processing condition requirements and a wider processing window. The formed polishing layer has a higher life stability. A polyamine composition and a polishing layer are further provided.